Demonstration of a Multi-Layer, Lithographically Manufactured Plasma Spectrometer

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Abstract

Development of new plasma instruments is needed to enable constellation- and small satellite-based missions. Key steps in the development pathway of ultra-compact plasma instruments employing lithographically patterned wafers are the implementation of layer-to-layer electrical interconnects and demonstration of massively parallel measurements, i.e., simultaneous measurements through multiple identical plasma analyzer structures. Here we present energy resolved measurements of electron beams using a 5-layer stack of wafer-based, energy-per-charge, electrostatic analyzers. Each layer has eight distinct analyzer groups that are comprised of multiple micron scale energy-per-charge analyzers. The process of fabricating the electrical interconnects between the layers is described and the measured energy resolution and the angular resolution compared to theoretical predictions. The measurements demonstrate successful operation of 400 micron scale analyzers operating in parallel.

Demonstration of a Multi-Layer, Lithographically Manufactured Plasma Spectrometer

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Key Points:

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- Microscale plasma energy analyzer demonstrated in laboratory tests
- Lithographic fabrication process enables low voltage analysis of charged particles up to tens of keV/charge
- Multi-layer instrument required development of a novel fabrication process

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13 Abstract

Development of new plasma instruments is needed to enable constellation- and small satellite-14 based missions. Key steps in the development pathway of ultra-compact plasma instru-15 ments employing lithographically patterned wafers are the implementation of layer-to-16 layer electrical interconnects and demonstration of massively parallel measurements, i.e., 17 simultaneous measurements through multiple identical plasma analyzer structures. Here 18 we present energy resolved measurements of electron beams using a 5-layer stack of wafer-19 based, energy-per-charge, electrostatic analyzers. Each layer has eight distinct analyzer 20 groups that are comprised of multiple micron scale energy-per-charge analyzers. The pro-21 cess of fabricating the electrical interconnects between the layers is described and the 22 measured energy resolution and the angular resolution compared to theoretical predic-23 tions. The measurements demonstrate successful operation of 400 micron scale analyz-24 ers operating in parallel. 25

²⁶ Plain Language Summary

Spacecraft are expensive and difficult to build. CubeSats, a class of small, inexpen-27 sive spacecraft are being used for scientific missions. However, standard instruments to 28 measure the local plasma environment cannot fit on such small spacecraft. Here we de-29 scribe a new type of space plasma instrument that is manufactured with processes sim-30 ilar to how computer chips are made. These plasma instruments are made by stacking 31 32 layers of micro-scale plasma analyzers to create a larger instrument with a significant geometric factor. Each layer includes nearly one hundred small energy-per-charge plasma 33 analyzers working in parallel. Initial measurements from a 5 layer instrument along with 34 the processes used to build the instrument are described in this work. 35

³⁶ 1 Introduction

Whether through opportunistic conjunctions or design, exploration of near-Earth 37 space has increasingly focused on understanding the energy flow and coupling between 38 different spatial regions through simultaneous measurements of essential plasma param-39 eters, e.g., magnetic field, electric field, density, and temperature, over the relevant spa-40 tial length scales. The International Solar Terrestrial Physics (ISTP) program's Wind, 41 Polar, and Geotail missions(Desch et al., 1997; Pulkkinen et al., 1997) and the THEMIS 42 mission(Angelopoulos, 2008) provided new insights and global perspectives on the flow 43 of energy from the solar wind through the magnetosphere. Though highly successful, those 44 missions were limited by rare conjunctions and sampling of only one place in each re-45 gion of the magnetosphere and upstream solar wind. Recent missions, e.g., Magnetospheric 46 Multiscale Mission (MMS)(Burch et al., 2016) and SWARM (Macmillan & Olsen, 2013) 47 have employed multiple spacecraft to resolve local gradients in plasma parameters and 48 to investigate kinetic scale phenomena. Such spatially resolved measurements are crit-49 ical for understanding the electrodynamics of different parts of the magnetosphere. 50

Upcoming missions, e.g., Helioswarm(Klein et al., 2023), will take advantage of ad-51 vances in the capabilities of CubeSat-scale instruments to minimize costs while launch-52 ing a constellation of 9 spacecraft. The 9 spacecraft CINEMA mission concept also re-53 cently advanced to the next round of NASA SMEX mission studies. (NASA, 2023) Look-54 ing beyond these scientific missions, it is possible to imagine deploying plasma instru-55 ments on hundreds to thousands of spacecraft if either the spacecraft are mass-produced 56 at low cost or if the instruments require so little resources that they could be included 57 on commercial spacecraft with little to no impact on the operation of those spacecraft. 58 With a truly massive (in number) constellation of instruments, it would be possible to 59 obtain simultaneous, high spatial resolution, vector field and plasma measurements over 60 a significant fraction of the magnetosphere. Such measurements could also be used as 61 inputs into real-time models of the near-Earth space environment. 62

However, the last generation of conventional plasma spectrometers, e.g., those flown 63 on MMS(Pollock et al., 2016), are too massive (roughly 6 kg), consume too much elec-64 trical power (several Watts), and require too much assembly and testing time to be flown 65 on future multi-spacecraft microsatellite missions (total spacecraft mass less than 10 kg 66 and total power less than 5 W (Frost, 2014)). The plasma instruments being developed 67 for Helioswarm require significantly reduced resources, but they are still manufactured 68 in the "classic" sense - through machining of metal parts and manual assembly. Advanced 69 wafer scale fabrication techniques naturally lend themselves to relatively high manufac-70 turing volumes and therefore change the paradigm for dealing with flaws or defects in 71 individual instruments. In other words, if it is possible to mass produce one thousand 72 low-cost plasma instruments, faulty units are simply thrown away and replaced with a 73 functional instrument before integration with the spacecraft. 74

There are essentially three elements in any plasma instrument: a collimating struc-75 ture that defines the field-of-view and, ideally, provides partial or complete shielding of 76 the instrument from sunlight; an energy per charge or energy per mass resolving ana-77 lyzer (this element could also be a simple time-of-flight detector that only measures par-78 ticle velocity); and a detector sensitive to charged particles in the desired energy range. 79 In previous studies we demonstrated the successful integration of a collimating structure 80 with an electrostatic analyzer at the wafer-scale level (Scime et al., 2016a, 2016b; Keesee 81 et al., 2018). Here we report the successful integration of multiple wafer layers and demon-82 stration of a functional, massively parallel, energy-per-charge electrostatic analyzer. 83



Figure 1. Photograph of a single Collimator and Energy Analyzer wafer or "layer." Across the top of image, the collimator section of the wafer is electrically isolated from the curved plate analyzer section. There are 8 energy analyzer bands, numbered from left to right, which consist of 10 channels (80 μ m wide) created by 9 fins (60 μ m wide). The outer two energy analyzer bands in this test wafer have straight channels for alignment purposes. The inner six bands have curved fins with a radii of 15 mm. The "mesas" in between the bands are the structures through which electrical interconnections are made. Barely visible in this image are the "through-silicon via" holes in the mesas that go through the glass substrate to complete the wafer-to-wafer connections. Three of the "through-silicon via" features are circled in red.

⁸⁴ 2 Instrumentation

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2.1 Single Layer Energy Analyzer and Collimator

Shown in Fig. 1 is a single layer combined Collimator and Energy Analyzer (CEA) 86 wafer or "layer." Every CEA wafer consists of eight electrostatic analyzer (EA) bands, 87 each with its own collimator section (top) that is mechanically and electrically isolated 88 from the EA section (bottom). Each EA band consists of 10 curved channels (80 μ m wide) 89 created by 9 fins (60 μ m wide and 360 μ m tall) with radii of 150 mm. Charged parti-90 cles enter at the top of the wafer, are collimated by the fins of the collimator section, travel 91 through the curved energy analyzer channels for energy selection, and then exit the bot-92 tom of the wafer to a detector. In this prototype wafer, the outer EA bands are straight 93 to facilitate alignment during testing. For the curved bands, charged particles of energy, 94 E, and charge, q, will pass through a channel of spacing, Δr , and radius of curvature, 95 R, for a voltage difference, V, across the channel such that 96

$$E = qV/(2ln(1 + \Delta r/R)). \tag{1}$$

For closely spaced plates, Eq. 1 reduces to $E = (qR\Delta V/(2\Delta r))$ to first order. Thus, 97 for 5 keV electrons, $\Delta r = 80 \mu m$, and R = 150 mm, the required voltage difference across 98 each gap is V = 5.33 Volts. To obtain that voltage across each gap, a total voltage difqq ference of 53.3 V is needed across the entire band of 10 channels. The collimator con-100 sists of identically spaced fins and outer tapered structures that limit the angular accep-101 tance of the flux entering each band to a nominal range of $\pm 5^{\circ}$. An important feature 102 of each wafer is that since the collimator fins are completely aligned with the EA fins, 103 the effective transparency of the collimator is 100%. Typically, the transparency of the 104 collimator is an additional loss term when calculating the total throughput (geometric 105 factor) of a plasma instrument. The collimator angular acceptance helps to define the 106 energy resolution of each band by limiting the range of possible trajectories through the 107 plates for charged particle energies that do not satisfy Eq. 1. Note also that the energy 108 analysis is accomplished with only modest voltages. Therefore, for the analyzer portion 109 of the instrument, no high voltage power supplies are required - which makes construc-110 tion of a variable energy analyzer bias supply (to sweep across multiple particle ener-111 gies) considerably easier. Because the potential difference applied between two plates is 112 at most a few volts, it is impossible to create an electrical discharge in between the plates 113 even though the electric field between two plates is large enough to deflect charged par-114 ticles of energies up to tens of keV/e (the voltage difference between any two plates is 115 comparable to or smaller than the ionization potential of atmospheric gasses and there-116 fore an ionization cascade is difficult to initiate). 117

The CEA chips were fabricated using a proprietary Deep Reactive Ion Etching (DRIE) 118 recipe developed by our team. The fins are etched in 360 μ m thick, heavily P/Boron doped 119 silicon on a 200 μ m glass substrate. The glass substrate serves as an etch stop and also 120 maintains electrical isolation. The bands in Fig. 1 are numbered 1-8 from the left and 121 the "mesas" between the bands are numbered from 0 to 8, again from the left. The highly 122 conductive silicon used for the fins and mesas has an electrical conductivity compara-123 ble to aluminum. A CEA built for a flight instrument would have all eight EA bands with 124 curved fins and with varying bias voltages applied to each band to obtain a eight-point 125 energy spectrum during each measurement interval. Since each energy band is contin-126 uously sampled, the duty factor for the energy analyzer at each energy is 100%. Note 127 the small circular features in the mesas in Fig. 1. Those features are the "through-silicon 128 via" (TSV) holes drilled through the entire wafer and then filled with a conductive ma-129 terial to create the wafer-to-wafer electric connections. The overall dimensions of the CEA 130 in Fig. 1 are 1.8 cm wide, 1.5 cm high, and 0.056 cm thick. 131

An ideal curved plate electrostatic analyzer would have curved fins that subtend 132 an angle of $127^{\circ}(\pi/\sqrt{2})$ to obtain first-order focusing of charged particles at the image 133 (detector) plane. The CEA shown here subtends a much smaller angle (just enough to 134 require photons to make a single bounce to pass through the instrument). Therefore, the 135 energy resolution of this instrument is worse than the nominal energy resolution of $\Delta E/E \sim$ 136 $\Delta r/R$ for an ideal curved plate analyzer, where ΔE is half the full width of the trans-137 mission function. The energy resolution could be improved by increasing the angle sub-138 tended by the curved fins at the expense of a more complicated geometry at the exit plane 139 of the wafer. 140

2.2 Wafer Stacking

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The full instrument is designed to employ 25 of these individual CEA wafers in a 142 single vertically integrated energy analyzer. Using double-sided lithography, a thin gold 143 electrode pattern with the same width and spacing of the fins and mesas is deposited 144 on the underside of each CEA wafer. In the collimator region, the entire underside re-145 gion is a single ground plane. The TSV holes connect the mesas to the electrode pat-146 tern on the underside of the wafer. There are multiple TSV connections in each mesa 147 to ensure a robust electrical connection. A boron hydride wire is deposited across the 148 entire underside electrode structure and serves as a voltage divider for each of the fins. 149 The fin and mesa structures on each wafer are coated with a 100 μ m thick capping layer 150 to couple the silicon structures to the electrode pattern on the underside of the wafer 151 above. With the addition of a final electrical breakout layer on the top of the stack, the 152 full 25 set of wafers is placed into a alignment mechanism and bonded together. Shown 153 in Fig. 2 is bonded set of 25 incompletely processed (so they are not fully functional) 154 wafers. The clear glass substrates facilitate viewing of the entire bonded structure. 155



Figure 2. Photograph of a bonded stack of 25 incompletely processed test wafers, each on a glass substrate. The dimensions of the full 25 stack are 1.8 cm wide, 1.5 cm deep, and 1.65 cm high.

To minimize current draw, the boron hydride resistor has a nominal mesa-to-mesa resistance of $1.4 \text{ M}\Omega$. With the voltage divider in place and assuming all eight energy

bands consistent of curved fins, six unique potentials applied to mesas 0-8 in a pattern 158 of 100 V, 50 V, 75 V, 0 V, 12.5 V, 17.5 V, 20 V, 0 V, and 100 V create nominal energy 159 passbands of 5 keV/e, 2.5 keV/e, 7.5 keV/e, 1.25 keV/e, 0.5 keV/e, 0.25 keV/e, 2 keV/e, 160 and 10 keV/e, respectively. Including the thickness of the capping layer, the dimensions 161 of the full 25 stack in Fig. 2 are 1.8 cm wide, 1.5 cm deep, and 1.65 cm high. For com-162 parison, a typical sugar cube has sides of 1 cm. Note that the 8 energy bands in all 25 163 layers operate in parallel. Therefore, a detector with 8 discrete regions of sensitivity placed 164 behind the energy analyzer (as shown in Fig. 3) would collect flux from all 25 layers si-165 multaneously. The conceptual detector shown in Fig. 3 is a commercially available 8 pixel 166 solid state detector. To overcome the energy threshold of the solid state detector, there 167 would need to be a postacceleration potential of 15-20 kV applied between the exit of 168 the analyzer and the front of the detector (or relative to a high transmission grid placed 169 in front of the detector). In this conceptual instrument design, the spacing between the 170 energy bands (and the overall width of each wafer) has been slightly modified to match 171 the spacing of the detector pixels in the commercial off-the-shelf (COTS) detector. 172



Figure 3. A schematic of 25 energy analyzer layers with an eight pixel solid state detector roughly 1 cm beyond the exit of the analyzer. The gap is placed between detector and analyzer so that a post acceleration potential of 10-20 kV between detector and analyzer will not arc across the gap. To match the spacing of the detector pixels, the band-to-band spacing in each of the wafers in this conceptual model has been increased slightly from that in Fig. 2.

¹⁷³ 3 Measurements of Electron Fluxes Through a 5-Layer Stack

As a first step in demonstrating the functionality of a multi-layer instrument, a fully 174 functional 5-stack assembly was fabricated, bonded into a single structure, and a ribbon 175 cable mounted to the top electrical breakout layer. Each of the wafers was a prototype 176 wafer as shown in Fig. 1, i.e., each wafer has 6 inner curved fin analyzer bands and the 177 outer two bands have straight fins. A full 5-stack assembly is shown in Fig. 4. A Quan-178 tar imaging microchannel plate (MCP) detector was mounted behind the 5-stack assem-179 bly to image the flux of charged particles that passed through the energy analyzer. To 180 prevent electrons from reaching the MCP directly, additional shields and a layer of alu-181 minium foil were placed around the 5-stack assembly. The entire assembly was then il-182 luminated with a variable energy electron beam (1 - 5 keV). Before the measurements, 183 the electron beam profile was measured with just the MCP to optimize the beam uni-184

- formity at the location of the measurement. The imaging MCP has a spatial resolution
- of approximately 65 μ m (the size of each channel in the MCP sensor).



Figure 4. An annotated photograph of a fully functional 5-layer stack before it was wired. The 5-layer stack is mounted on a test structure to which an imaging microchannel plate (MCP) detector is later mounted.

Shown in Fig. 5 are two MCP images of the flux of 3 keV electrons passing through 187 the 5-stack assembly for a voltage difference of 37 V applied to the inner six bands and 188 0 V applied across the outer two bands. There are a number of important features in 189 these figures. First, the maximum flux through the energy analyzer was obtained at ex-190 actly the bias potential predicted by Eq. 1. Second, in Fig. 5a, there are three clearly 191 identifiable layers through which flux is passing. In Fig. 5b, the the fourth layer appears 192 in all four signal regions. There is a hint of a fifth layer in the two signal regions to the 193 right of the image. Because of the coarse nature of the tilt angle stage to which the 5-194 stack assembly was mounted, it was difficult to reliably align the assembly so that all 195 4 (sometimes 5) layers were illuminated. The angular precision needed, as will be dis-196 cussed later, was less than 1°. In the initial measurements, there was a thin piece of alu-197 minium foil that was placed near the top layer of the analyzer when the image in Fig. 198 5a was recorded. It is possible that the foil was blocking the top two layers. The foil was 199 removed for the image in Fig. 5b, but all five layers were still not visible. Two other is-200 sues could have prevented full illumination of all 5 layers. First, when the electrical break-201 out layer at the top of the stack was bonded to the stack, it is possible that some of the 202 capping layer material seeped into the channels of the bands. Second, there is a mod-203 est divergence of the electron beam. Thus, electrons with a velocity component perpen-204 dicular to the beam axis will be blocked by the relatively narrow angular acceptance of 205 the energy analyzer. In practice, the ambient electron populations in space are superther-206 mal and electron flux comes from all directions around the instrument. In other words, 207 an instrument like this in space would be illuminated from all directions and beam di-208 vergence issues would not impact performance. 209

Another important feature in the images is that only four regions of signal appear instead of the eight that would be expected for the eight energy bands. Notice also that the outer signal regions are significantly wider than the two inner signal regions. The



Figure 5. Imaging microchannel plate (MCP) measurements of 3 keV electron flux through a 5-stack energy analyzer. (a) Electron beam illuminating the lower 3 layers of the 5-stack. (b) After removal of some blocking aluminium foil and more careful alignment of the 5-stack assembly to the electron beam, 4 full layers were seen across all 8 bands and hints of the 5^{th} layer are evident in the two signal regions to the right of the image.

measured flux pattern results from the serendipitous placement of the MCP detector rel-213 ative to the exits of the eight energy bands. Comparing the measured flux pattern to the 214 energy band locations shown in Fig. 1, it is clear that the inner two signal regions re-215 sult from the overlap of energy bands with opposite curvatures. By placing the MCP at 216 the distance at which the flux exiting two bands fully overlap, the signal from both bands 217 is measured at the same location on the MCP. To passively separate the flux from the 218 two bands, the imaging MCP would have to be placed much closer to the exits of the 219 5-stack (before the fluxes overlap) or much further away (after the fluxes pass through 220 each other and become distinguishable again. SIMION[™]simulations of the combined en-221 ergy analyzer and detector assembly shown in Fig. 3, show that active separation of the 222 fluxes from two bands of opposite curvature is possible if a 10-20 kV post-acceleration 223 potential is placed at the exit of the energy analyzer. The fluxes from adjacent curved 224 channels are then easily directed to distinct regions on the segmented detector. The two 225 outer signal regions in Fig. 5 are wider because for this prototype energy analyzer, the 226 two outermost energy bands have straight fins. Therefore, fluxes from an outer band and 227 the curved band next to it are adjacent but do not fully overlap for the energy analyzer-228 to-MCP spacing used in these measurements. Thus, the signal regions from left to right 229 in Fig. 5 are from (B1 + B2), (B3 + B4), (B5 + B6), and (B7 + B8). 230

To confirm that the energy selection properties of the 5-stack were consistent with 231 predictions based on the geometry of the structures, the potential difference required to 232 maximize the transmitted electron flux was measured for four different electron beam 233 energies. All of the energy bands were set to transmit the same beam energy and only 234 the fluxes transmitted through the inner four energy bands were measured. As shown 235 in Fig. 6a, the bias voltage measurements for the 5-stack energy analyzer are well fit by 236 a linear relationship. The slope of the fit yields an applied bias to energy per charge scal-237 ing relationship that is within 10% of the predicted value. As noted previously, the en-238



Figure 6. (a) Energy analyzer bias voltage required to maximize the transmitted flux as a function of electron beam energy. The solid line is the predicted scaling of the energy analyzer (Eq. 1) a function of transmitted beam energy. (b) Measured energy resolution as a function of beam energy. Each measurement is based on measurements of the transmitted electron flux for a fixed beam energy versus energy analyzer bias voltage, e.g. the 4 keV beam example shown in the insert.

ergy resolution of each energy band is worse than it would be for an ideal 127° analyzer. 239 Based on SIMIONTM simulations of a full energy band structure, the expected energy 240 resolution of a single analyzer band is approximately 20%. Shown in Fig. 6b are the mea-241 sured energy resolutions for four different electron beam energies transmitted through 242 the inner four energy bands. Each measurement is based on the HWHM of a Gaussian 243 fit to the measured flux for a fixed beam energy $(\Delta V/V)$ as a function of bias voltage 244 applied to the energy analyzer (see insert in Fig. 6b). The relatively poor energy res-245 olution results from the limited curvature of each fin. The nominal 20% energy resolu-246 tion is, however, completely consistent with the modeling predictions and previous mea-247 surements of single layer transmission (Scime et al., 2016a, 2016b). 248

The transmitted electron flux for a beam energy of 3 keV as a function of rotation 249 angle around the normal to the plane of layer (azimuthal angle) and the tilt angle of the 250 wafer relative to the axis of the electron beam (pitch) are shown in Fig. 7a and b, re-251 spectively. Again, only the transmitted fluxes for the four inner energy bands were used 252 in the measurements. For the azimuthal angle measurements, the expected angular res-253 olution is estimated from the fin-to-fin spacing and the overall length of each curved fin 254 (the collimator acceptance of $\pm 5^{\circ}$ is much larger than the angular acceptance of each 255 curved pathway). From $\tan \theta = \Delta r/L$, where $L = 100 \ \mu m$, the estimated azimuthal 256 angular acceptance is $\pm 0.5^{\circ}$. A Gaussian fit to the transmitted flux data of Fig. 7a yields 257 measured azimuthal angular acceptance of $\pm 0.79^{\circ}$ - slightly larger than the predicted 258 value. The angular acceptance of the instrument in the pitch direction should be much 259 larger than in the azimuthal direction because the height of the fins is roughly four times 260 larger than the fin-to-fin spacing. However, the measured angular acceptance in the pitch 261 direction (Fig. 7b) is comparable to the azimuthal angular resolution ($\sim \pm 0.89^{\circ}$). The 262 measurements are of modest quality since, as noted previously, the motion stage used 263 for the pitch angle measurements had poor resolution and repeatability in the pitch di-264 rection. Hints of similar results for pitch angular acceptance were reported in previous 265 measurements of a single CEA layer (Keesee et al., 2018). The reason for the limited pitch 266

angular resolution is not clear. The MCP images (Fig. 5) suggest that electrons are coming through the full vertical span of the channels when the entrance apertures are fully
illuminated, at least for 4 of the layers. One possibility is that the electron beam divergence in the pitch direction is larger than assumed. However, the previous single CEA
layer measurements and these 5-stack measurements employed different electron beam
sources, so it is unlikely that both sources had anomalously large beam divergences in
the pitch direction.



Figure 7. (a) Transmitted flux through the inner four energy bands as a function of azimuthal angle (rotation axis around the normal to the layers). (b) Transmitted flux through the inner four energy bands as a function of pitch angle (tilt of the layer plane relative to the nominal beam direction).

²⁷⁴ 4 Conclusions

A multi-layer, lithographically fabricated plasma spectrometer has been fabricated 275 and demonstrated to accurately measure the energy per charge of a 1 - 5 keV electron 276 beam. The 5-layer instrument demonstrated is a prototype of a 25 layer instrument that 277 will have nominal dimensions of $1.5 \ge 1.5 \ge 1.5 \ge 1.5 \ge 1.5$ cm³. The 5-layer prototype consisted of 278 400 individual E/q analyzers operating in parallel to create a miniaturized instrument 279 with an estimated per pixel (per viewing direction), per energy band, geometric factor 280 on the order of $G = 1.6 \times 10^{-5} cm^2$ sr (eV/eV) for the full 25 layer instrument (Scime 281 et al., 2016a). For comparison, the FPI instrument for MMS has a geometric factor of 282 $G = 2 \times 10^{-4} cm^2$ sr (eV/eV) per imaging pixel at 20 keV (Collinson et al., 2012). In 283 other words, were the full 25-layer instrument to be placed into the same orbit as the 284 MMS spacecraft, the expected count rate in each imaging direction would be 10% of that 285 of the FPI instrument. 286

To increase the spatial coverage or the overall geometric factor of this type of in-287 strument, a collection of these ultra-compact plasma spectrometers could be used in par-288 allel. Note that the geometric factor of this type of instrument scales linearly with any 289 dimension of the instrument, whereas conventional instruments grow in volume as the 290 surface area of the aperture increases. In other words, one hundred, e.g., a 10 by 10 ar-291 ray, of these ultra-compact plasma spectrometers placed on the side of a CubeSat would 292 have a geometric factor ten times larger than a conventional plasma spectrometer but 293 would still only be a panel approximately 15 cm x 17.5 cm in area and 1.5 cm thick. All 294 one hundred ultra-compact spectrometers could share the same power supplies and read-295

²⁹⁶ out electronics. Were all six sides of a single unit CubeSat to be covered with such pan-²⁹⁷ els, such a collection of plasma spectrometers could provide six measurements through ²⁹⁸ a full three-dimensional particle velocity distribution with a substantial count rate.

We note that the energy per charge scaling, angular resolution, and energy resolution of the energy analyzer are in excellent agreement with the design targets. The fabrication steps developed to make the electrical interconnections between the layers were successful and these results demonstrate that multi-layer, lithgraphically fabricated plasma spectrometers are ready to be mated to solid state detectors with postacceleration to create robust instruments amenable to large-volume manufacturing.

³⁰⁵ Open Research Section

The data that support the findings of this study are openly available in Zenodo at https://doi.org/10.5281/zenodo.8406445.

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- Microscale plasma energy analyzer demonstrated in laboratory tests
- Lithographic fabrication process enables low voltage analysis of charged particles up to tens of keV/charge
- Multi-layer instrument required development of a novel fabrication process

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13 Abstract

Development of new plasma instruments is needed to enable constellation- and small satellite-14 based missions. Key steps in the development pathway of ultra-compact plasma instru-15 ments employing lithographically patterned wafers are the implementation of layer-to-16 layer electrical interconnects and demonstration of massively parallel measurements, i.e., 17 simultaneous measurements through multiple identical plasma analyzer structures. Here 18 we present energy resolved measurements of electron beams using a 5-layer stack of wafer-19 based, energy-per-charge, electrostatic analyzers. Each layer has eight distinct analyzer 20 groups that are comprised of multiple micron scale energy-per-charge analyzers. The pro-21 cess of fabricating the electrical interconnects between the layers is described and the 22 measured energy resolution and the angular resolution compared to theoretical predic-23 tions. The measurements demonstrate successful operation of 400 micron scale analyz-24 ers operating in parallel. 25

²⁶ Plain Language Summary

Spacecraft are expensive and difficult to build. CubeSats, a class of small, inexpen-27 sive spacecraft are being used for scientific missions. However, standard instruments to 28 measure the local plasma environment cannot fit on such small spacecraft. Here we de-29 scribe a new type of space plasma instrument that is manufactured with processes sim-30 ilar to how computer chips are made. These plasma instruments are made by stacking 31 32 layers of micro-scale plasma analyzers to create a larger instrument with a significant geometric factor. Each layer includes nearly one hundred small energy-per-charge plasma 33 analyzers working in parallel. Initial measurements from a 5 layer instrument along with 34 the processes used to build the instrument are described in this work. 35

³⁶ 1 Introduction

Whether through opportunistic conjunctions or design, exploration of near-Earth 37 space has increasingly focused on understanding the energy flow and coupling between 38 different spatial regions through simultaneous measurements of essential plasma param-39 eters, e.g., magnetic field, electric field, density, and temperature, over the relevant spa-40 tial length scales. The International Solar Terrestrial Physics (ISTP) program's Wind, 41 Polar, and Geotail missions(Desch et al., 1997; Pulkkinen et al., 1997) and the THEMIS 42 mission(Angelopoulos, 2008) provided new insights and global perspectives on the flow 43 of energy from the solar wind through the magnetosphere. Though highly successful, those 44 missions were limited by rare conjunctions and sampling of only one place in each re-45 gion of the magnetosphere and upstream solar wind. Recent missions, e.g., Magnetospheric 46 Multiscale Mission (MMS)(Burch et al., 2016) and SWARM (Macmillan & Olsen, 2013) 47 have employed multiple spacecraft to resolve local gradients in plasma parameters and 48 to investigate kinetic scale phenomena. Such spatially resolved measurements are crit-49 ical for understanding the electrodynamics of different parts of the magnetosphere. 50

Upcoming missions, e.g., Helioswarm(Klein et al., 2023), will take advantage of ad-51 vances in the capabilities of CubeSat-scale instruments to minimize costs while launch-52 ing a constellation of 9 spacecraft. The 9 spacecraft CINEMA mission concept also re-53 cently advanced to the next round of NASA SMEX mission studies. (NASA, 2023) Look-54 ing beyond these scientific missions, it is possible to imagine deploying plasma instru-55 ments on hundreds to thousands of spacecraft if either the spacecraft are mass-produced 56 at low cost or if the instruments require so little resources that they could be included 57 on commercial spacecraft with little to no impact on the operation of those spacecraft. 58 With a truly massive (in number) constellation of instruments, it would be possible to 59 obtain simultaneous, high spatial resolution, vector field and plasma measurements over 60 a significant fraction of the magnetosphere. Such measurements could also be used as 61 inputs into real-time models of the near-Earth space environment. 62

However, the last generation of conventional plasma spectrometers, e.g., those flown 63 on MMS(Pollock et al., 2016), are too massive (roughly 6 kg), consume too much elec-64 trical power (several Watts), and require too much assembly and testing time to be flown 65 on future multi-spacecraft microsatellite missions (total spacecraft mass less than 10 kg 66 and total power less than 5 W (Frost, 2014)). The plasma instruments being developed 67 for Helioswarm require significantly reduced resources, but they are still manufactured 68 in the "classic" sense - through machining of metal parts and manual assembly. Advanced 69 wafer scale fabrication techniques naturally lend themselves to relatively high manufac-70 turing volumes and therefore change the paradigm for dealing with flaws or defects in 71 individual instruments. In other words, if it is possible to mass produce one thousand 72 low-cost plasma instruments, faulty units are simply thrown away and replaced with a 73 functional instrument before integration with the spacecraft. 74

There are essentially three elements in any plasma instrument: a collimating struc-75 ture that defines the field-of-view and, ideally, provides partial or complete shielding of 76 the instrument from sunlight; an energy per charge or energy per mass resolving ana-77 lyzer (this element could also be a simple time-of-flight detector that only measures par-78 ticle velocity); and a detector sensitive to charged particles in the desired energy range. 79 In previous studies we demonstrated the successful integration of a collimating structure 80 with an electrostatic analyzer at the wafer-scale level (Scime et al., 2016a, 2016b; Keesee 81 et al., 2018). Here we report the successful integration of multiple wafer layers and demon-82 stration of a functional, massively parallel, energy-per-charge electrostatic analyzer. 83



Figure 1. Photograph of a single Collimator and Energy Analyzer wafer or "layer." Across the top of image, the collimator section of the wafer is electrically isolated from the curved plate analyzer section. There are 8 energy analyzer bands, numbered from left to right, which consist of 10 channels (80 μ m wide) created by 9 fins (60 μ m wide). The outer two energy analyzer bands in this test wafer have straight channels for alignment purposes. The inner six bands have curved fins with a radii of 15 mm. The "mesas" in between the bands are the structures through which electrical interconnections are made. Barely visible in this image are the "through-silicon via" holes in the mesas that go through the glass substrate to complete the wafer-to-wafer connections. Three of the "through-silicon via" features are circled in red.

⁸⁴ 2 Instrumentation

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2.1 Single Layer Energy Analyzer and Collimator

Shown in Fig. 1 is a single layer combined Collimator and Energy Analyzer (CEA) 86 wafer or "layer." Every CEA wafer consists of eight electrostatic analyzer (EA) bands, 87 each with its own collimator section (top) that is mechanically and electrically isolated 88 from the EA section (bottom). Each EA band consists of 10 curved channels (80 μ m wide) 89 created by 9 fins (60 μ m wide and 360 μ m tall) with radii of 150 mm. Charged parti-90 cles enter at the top of the wafer, are collimated by the fins of the collimator section, travel 91 through the curved energy analyzer channels for energy selection, and then exit the bot-92 tom of the wafer to a detector. In this prototype wafer, the outer EA bands are straight 93 to facilitate alignment during testing. For the curved bands, charged particles of energy, 94 E, and charge, q, will pass through a channel of spacing, Δr , and radius of curvature, 95 R, for a voltage difference, V, across the channel such that 96

$$E = qV/(2ln(1 + \Delta r/R)). \tag{1}$$

For closely spaced plates, Eq. 1 reduces to $E = (qR\Delta V/(2\Delta r))$ to first order. Thus, 97 for 5 keV electrons, $\Delta r = 80 \mu m$, and R = 150 mm, the required voltage difference across 98 each gap is V = 5.33 Volts. To obtain that voltage across each gap, a total voltage difqq ference of 53.3 V is needed across the entire band of 10 channels. The collimator con-100 sists of identically spaced fins and outer tapered structures that limit the angular accep-101 tance of the flux entering each band to a nominal range of $\pm 5^{\circ}$. An important feature 102 of each wafer is that since the collimator fins are completely aligned with the EA fins, 103 the effective transparency of the collimator is 100%. Typically, the transparency of the 104 collimator is an additional loss term when calculating the total throughput (geometric 105 factor) of a plasma instrument. The collimator angular acceptance helps to define the 106 energy resolution of each band by limiting the range of possible trajectories through the 107 plates for charged particle energies that do not satisfy Eq. 1. Note also that the energy 108 analysis is accomplished with only modest voltages. Therefore, for the analyzer portion 109 of the instrument, no high voltage power supplies are required - which makes construc-110 tion of a variable energy analyzer bias supply (to sweep across multiple particle ener-111 gies) considerably easier. Because the potential difference applied between two plates is 112 at most a few volts, it is impossible to create an electrical discharge in between the plates 113 even though the electric field between two plates is large enough to deflect charged par-114 ticles of energies up to tens of keV/e (the voltage difference between any two plates is 115 comparable to or smaller than the ionization potential of atmospheric gasses and there-116 fore an ionization cascade is difficult to initiate). 117

The CEA chips were fabricated using a proprietary Deep Reactive Ion Etching (DRIE) 118 recipe developed by our team. The fins are etched in 360 μ m thick, heavily P/Boron doped 119 silicon on a 200 μ m glass substrate. The glass substrate serves as an etch stop and also 120 maintains electrical isolation. The bands in Fig. 1 are numbered 1-8 from the left and 121 the "mesas" between the bands are numbered from 0 to 8, again from the left. The highly 122 conductive silicon used for the fins and mesas has an electrical conductivity compara-123 ble to aluminum. A CEA built for a flight instrument would have all eight EA bands with 124 curved fins and with varying bias voltages applied to each band to obtain a eight-point 125 energy spectrum during each measurement interval. Since each energy band is contin-126 uously sampled, the duty factor for the energy analyzer at each energy is 100%. Note 127 the small circular features in the mesas in Fig. 1. Those features are the "through-silicon 128 via" (TSV) holes drilled through the entire wafer and then filled with a conductive ma-129 terial to create the wafer-to-wafer electric connections. The overall dimensions of the CEA 130 in Fig. 1 are 1.8 cm wide, 1.5 cm high, and 0.056 cm thick. 131

An ideal curved plate electrostatic analyzer would have curved fins that subtend 132 an angle of $127^{\circ}(\pi/\sqrt{2})$ to obtain first-order focusing of charged particles at the image 133 (detector) plane. The CEA shown here subtends a much smaller angle (just enough to 134 require photons to make a single bounce to pass through the instrument). Therefore, the 135 energy resolution of this instrument is worse than the nominal energy resolution of $\Delta E/E \sim$ 136 $\Delta r/R$ for an ideal curved plate analyzer, where ΔE is half the full width of the trans-137 mission function. The energy resolution could be improved by increasing the angle sub-138 tended by the curved fins at the expense of a more complicated geometry at the exit plane 139 of the wafer. 140

2.2 Wafer Stacking

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The full instrument is designed to employ 25 of these individual CEA wafers in a 142 single vertically integrated energy analyzer. Using double-sided lithography, a thin gold 143 electrode pattern with the same width and spacing of the fins and mesas is deposited 144 on the underside of each CEA wafer. In the collimator region, the entire underside re-145 gion is a single ground plane. The TSV holes connect the mesas to the electrode pat-146 tern on the underside of the wafer. There are multiple TSV connections in each mesa 147 to ensure a robust electrical connection. A boron hydride wire is deposited across the 148 entire underside electrode structure and serves as a voltage divider for each of the fins. 149 The fin and mesa structures on each wafer are coated with a 100 μ m thick capping layer 150 to couple the silicon structures to the electrode pattern on the underside of the wafer 151 above. With the addition of a final electrical breakout layer on the top of the stack, the 152 full 25 set of wafers is placed into a alignment mechanism and bonded together. Shown 153 in Fig. 2 is bonded set of 25 incompletely processed (so they are not fully functional) 154 wafers. The clear glass substrates facilitate viewing of the entire bonded structure. 155



Figure 2. Photograph of a bonded stack of 25 incompletely processed test wafers, each on a glass substrate. The dimensions of the full 25 stack are 1.8 cm wide, 1.5 cm deep, and 1.65 cm high.

To minimize current draw, the boron hydride resistor has a nominal mesa-to-mesa resistance of $1.4 \text{ M}\Omega$. With the voltage divider in place and assuming all eight energy

bands consistent of curved fins, six unique potentials applied to mesas 0-8 in a pattern 158 of 100 V, 50 V, 75 V, 0 V, 12.5 V, 17.5 V, 20 V, 0 V, and 100 V create nominal energy 159 passbands of 5 keV/e, 2.5 keV/e, 7.5 keV/e, 1.25 keV/e, 0.5 keV/e, 0.25 keV/e, 2 keV/e, 160 and 10 keV/e, respectively. Including the thickness of the capping layer, the dimensions 161 of the full 25 stack in Fig. 2 are 1.8 cm wide, 1.5 cm deep, and 1.65 cm high. For com-162 parison, a typical sugar cube has sides of 1 cm. Note that the 8 energy bands in all 25 163 layers operate in parallel. Therefore, a detector with 8 discrete regions of sensitivity placed 164 behind the energy analyzer (as shown in Fig. 3) would collect flux from all 25 layers si-165 multaneously. The conceptual detector shown in Fig. 3 is a commercially available 8 pixel 166 solid state detector. To overcome the energy threshold of the solid state detector, there 167 would need to be a postacceleration potential of 15-20 kV applied between the exit of 168 the analyzer and the front of the detector (or relative to a high transmission grid placed 169 in front of the detector). In this conceptual instrument design, the spacing between the 170 energy bands (and the overall width of each wafer) has been slightly modified to match 171 the spacing of the detector pixels in the commercial off-the-shelf (COTS) detector. 172



Figure 3. A schematic of 25 energy analyzer layers with an eight pixel solid state detector roughly 1 cm beyond the exit of the analyzer. The gap is placed between detector and analyzer so that a post acceleration potential of 10-20 kV between detector and analyzer will not arc across the gap. To match the spacing of the detector pixels, the band-to-band spacing in each of the wafers in this conceptual model has been increased slightly from that in Fig. 2.

¹⁷³ 3 Measurements of Electron Fluxes Through a 5-Layer Stack

As a first step in demonstrating the functionality of a multi-layer instrument, a fully 174 functional 5-stack assembly was fabricated, bonded into a single structure, and a ribbon 175 cable mounted to the top electrical breakout layer. Each of the wafers was a prototype 176 wafer as shown in Fig. 1, i.e., each wafer has 6 inner curved fin analyzer bands and the 177 outer two bands have straight fins. A full 5-stack assembly is shown in Fig. 4. A Quan-178 tar imaging microchannel plate (MCP) detector was mounted behind the 5-stack assem-179 bly to image the flux of charged particles that passed through the energy analyzer. To 180 prevent electrons from reaching the MCP directly, additional shields and a layer of alu-181 minium foil were placed around the 5-stack assembly. The entire assembly was then il-182 luminated with a variable energy electron beam (1 - 5 keV). Before the measurements, 183 the electron beam profile was measured with just the MCP to optimize the beam uni-184

- formity at the location of the measurement. The imaging MCP has a spatial resolution
- of approximately 65 μ m (the size of each channel in the MCP sensor).



Figure 4. An annotated photograph of a fully functional 5-layer stack before it was wired. The 5-layer stack is mounted on a test structure to which an imaging microchannel plate (MCP) detector is later mounted.

Shown in Fig. 5 are two MCP images of the flux of 3 keV electrons passing through 187 the 5-stack assembly for a voltage difference of 37 V applied to the inner six bands and 188 0 V applied across the outer two bands. There are a number of important features in 189 these figures. First, the maximum flux through the energy analyzer was obtained at ex-190 actly the bias potential predicted by Eq. 1. Second, in Fig. 5a, there are three clearly 191 identifiable layers through which flux is passing. In Fig. 5b, the the fourth layer appears 192 in all four signal regions. There is a hint of a fifth layer in the two signal regions to the 193 right of the image. Because of the coarse nature of the tilt angle stage to which the 5-194 stack assembly was mounted, it was difficult to reliably align the assembly so that all 195 4 (sometimes 5) layers were illuminated. The angular precision needed, as will be dis-196 cussed later, was less than 1°. In the initial measurements, there was a thin piece of alu-197 minium foil that was placed near the top layer of the analyzer when the image in Fig. 198 5a was recorded. It is possible that the foil was blocking the top two layers. The foil was 199 removed for the image in Fig. 5b, but all five layers were still not visible. Two other is-200 sues could have prevented full illumination of all 5 layers. First, when the electrical break-201 out layer at the top of the stack was bonded to the stack, it is possible that some of the 202 capping layer material seeped into the channels of the bands. Second, there is a mod-203 est divergence of the electron beam. Thus, electrons with a velocity component perpen-204 dicular to the beam axis will be blocked by the relatively narrow angular acceptance of 205 the energy analyzer. In practice, the ambient electron populations in space are superther-206 mal and electron flux comes from all directions around the instrument. In other words, 207 an instrument like this in space would be illuminated from all directions and beam di-208 vergence issues would not impact performance. 209

Another important feature in the images is that only four regions of signal appear instead of the eight that would be expected for the eight energy bands. Notice also that the outer signal regions are significantly wider than the two inner signal regions. The



Figure 5. Imaging microchannel plate (MCP) measurements of 3 keV electron flux through a 5-stack energy analyzer. (a) Electron beam illuminating the lower 3 layers of the 5-stack. (b) After removal of some blocking aluminium foil and more careful alignment of the 5-stack assembly to the electron beam, 4 full layers were seen across all 8 bands and hints of the 5^{th} layer are evident in the two signal regions to the right of the image.

measured flux pattern results from the serendipitous placement of the MCP detector rel-213 ative to the exits of the eight energy bands. Comparing the measured flux pattern to the 214 energy band locations shown in Fig. 1, it is clear that the inner two signal regions re-215 sult from the overlap of energy bands with opposite curvatures. By placing the MCP at 216 the distance at which the flux exiting two bands fully overlap, the signal from both bands 217 is measured at the same location on the MCP. To passively separate the flux from the 218 two bands, the imaging MCP would have to be placed much closer to the exits of the 219 5-stack (before the fluxes overlap) or much further away (after the fluxes pass through 220 each other and become distinguishable again. SIMION[™]simulations of the combined en-221 ergy analyzer and detector assembly shown in Fig. 3, show that active separation of the 222 fluxes from two bands of opposite curvature is possible if a 10-20 kV post-acceleration 223 potential is placed at the exit of the energy analyzer. The fluxes from adjacent curved 224 channels are then easily directed to distinct regions on the segmented detector. The two 225 outer signal regions in Fig. 5 are wider because for this prototype energy analyzer, the 226 two outermost energy bands have straight fins. Therefore, fluxes from an outer band and 227 the curved band next to it are adjacent but do not fully overlap for the energy analyzer-228 to-MCP spacing used in these measurements. Thus, the signal regions from left to right 229 in Fig. 5 are from (B1 + B2), (B3 + B4), (B5 + B6), and (B7 + B8). 230

To confirm that the energy selection properties of the 5-stack were consistent with 231 predictions based on the geometry of the structures, the potential difference required to 232 maximize the transmitted electron flux was measured for four different electron beam 233 energies. All of the energy bands were set to transmit the same beam energy and only 234 the fluxes transmitted through the inner four energy bands were measured. As shown 235 in Fig. 6a, the bias voltage measurements for the 5-stack energy analyzer are well fit by 236 a linear relationship. The slope of the fit yields an applied bias to energy per charge scal-237 ing relationship that is within 10% of the predicted value. As noted previously, the en-238



Figure 6. (a) Energy analyzer bias voltage required to maximize the transmitted flux as a function of electron beam energy. The solid line is the predicted scaling of the energy analyzer (Eq. 1) a function of transmitted beam energy. (b) Measured energy resolution as a function of beam energy. Each measurement is based on measurements of the transmitted electron flux for a fixed beam energy versus energy analyzer bias voltage, e.g. the 4 keV beam example shown in the insert.

ergy resolution of each energy band is worse than it would be for an ideal 127° analyzer. 239 Based on SIMIONTM simulations of a full energy band structure, the expected energy 240 resolution of a single analyzer band is approximately 20%. Shown in Fig. 6b are the mea-241 sured energy resolutions for four different electron beam energies transmitted through 242 the inner four energy bands. Each measurement is based on the HWHM of a Gaussian 243 fit to the measured flux for a fixed beam energy $(\Delta V/V)$ as a function of bias voltage 244 applied to the energy analyzer (see insert in Fig. 6b). The relatively poor energy res-245 olution results from the limited curvature of each fin. The nominal 20% energy resolu-246 tion is, however, completely consistent with the modeling predictions and previous mea-247 surements of single layer transmission (Scime et al., 2016a, 2016b). 248

The transmitted electron flux for a beam energy of 3 keV as a function of rotation 249 angle around the normal to the plane of layer (azimuthal angle) and the tilt angle of the 250 wafer relative to the axis of the electron beam (pitch) are shown in Fig. 7a and b, re-251 spectively. Again, only the transmitted fluxes for the four inner energy bands were used 252 in the measurements. For the azimuthal angle measurements, the expected angular res-253 olution is estimated from the fin-to-fin spacing and the overall length of each curved fin 254 (the collimator acceptance of $\pm 5^{\circ}$ is much larger than the angular acceptance of each 255 curved pathway). From $\tan \theta = \Delta r/L$, where $L = 100 \ \mu m$, the estimated azimuthal 256 angular acceptance is $\pm 0.5^{\circ}$. A Gaussian fit to the transmitted flux data of Fig. 7a yields 257 measured azimuthal angular acceptance of $\pm 0.79^{\circ}$ - slightly larger than the predicted 258 value. The angular acceptance of the instrument in the pitch direction should be much 259 larger than in the azimuthal direction because the height of the fins is roughly four times 260 larger than the fin-to-fin spacing. However, the measured angular acceptance in the pitch 261 direction (Fig. 7b) is comparable to the azimuthal angular resolution ($\sim \pm 0.89^{\circ}$). The 262 measurements are of modest quality since, as noted previously, the motion stage used 263 for the pitch angle measurements had poor resolution and repeatability in the pitch di-264 rection. Hints of similar results for pitch angular acceptance were reported in previous 265 measurements of a single CEA layer (Keesee et al., 2018). The reason for the limited pitch 266

angular resolution is not clear. The MCP images (Fig. 5) suggest that electrons are coming through the full vertical span of the channels when the entrance apertures are fully
illuminated, at least for 4 of the layers. One possibility is that the electron beam divergence in the pitch direction is larger than assumed. However, the previous single CEA
layer measurements and these 5-stack measurements employed different electron beam
sources, so it is unlikely that both sources had anomalously large beam divergences in
the pitch direction.



Figure 7. (a) Transmitted flux through the inner four energy bands as a function of azimuthal angle (rotation axis around the normal to the layers). (b) Transmitted flux through the inner four energy bands as a function of pitch angle (tilt of the layer plane relative to the nominal beam direction).

²⁷⁴ 4 Conclusions

A multi-layer, lithographically fabricated plasma spectrometer has been fabricated 275 and demonstrated to accurately measure the energy per charge of a 1 - 5 keV electron 276 beam. The 5-layer instrument demonstrated is a prototype of a 25 layer instrument that 277 will have nominal dimensions of $1.5 \ge 1.5 \ge 1.5 \ge 1.5 \ge 1.5$ cm³. The 5-layer prototype consisted of 278 400 individual E/q analyzers operating in parallel to create a miniaturized instrument 279 with an estimated per pixel (per viewing direction), per energy band, geometric factor 280 on the order of $G = 1.6 \times 10^{-5} cm^2$ sr (eV/eV) for the full 25 layer instrument (Scime 281 et al., 2016a). For comparison, the FPI instrument for MMS has a geometric factor of 282 $G = 2 \times 10^{-4} cm^2$ sr (eV/eV) per imaging pixel at 20 keV (Collinson et al., 2012). In 283 other words, were the full 25-layer instrument to be placed into the same orbit as the 284 MMS spacecraft, the expected count rate in each imaging direction would be 10% of that 285 of the FPI instrument. 286

To increase the spatial coverage or the overall geometric factor of this type of in-287 strument, a collection of these ultra-compact plasma spectrometers could be used in par-288 allel. Note that the geometric factor of this type of instrument scales linearly with any 289 dimension of the instrument, whereas conventional instruments grow in volume as the 290 surface area of the aperture increases. In other words, one hundred, e.g., a 10 by 10 ar-291 ray, of these ultra-compact plasma spectrometers placed on the side of a CubeSat would 292 have a geometric factor ten times larger than a conventional plasma spectrometer but 293 would still only be a panel approximately 15 cm x 17.5 cm in area and 1.5 cm thick. All 294 one hundred ultra-compact spectrometers could share the same power supplies and read-295

²⁹⁶ out electronics. Were all six sides of a single unit CubeSat to be covered with such pan-²⁹⁷ els, such a collection of plasma spectrometers could provide six measurements through ²⁹⁸ a full three-dimensional particle velocity distribution with a substantial count rate.

We note that the energy per charge scaling, angular resolution, and energy resolution of the energy analyzer are in excellent agreement with the design targets. The fabrication steps developed to make the electrical interconnections between the layers were successful and these results demonstrate that multi-layer, lithgraphically fabricated plasma spectrometers are ready to be mated to solid state detectors with postacceleration to create robust instruments amenable to large-volume manufacturing.

³⁰⁵ Open Research Section

The data that support the findings of this study are openly available in Zenodo at https://doi.org/10.5281/zenodo.8406445.

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